

HS-6664RH

Radiation Hardened 8K x 8 CMOS PROM

September 1995

Features

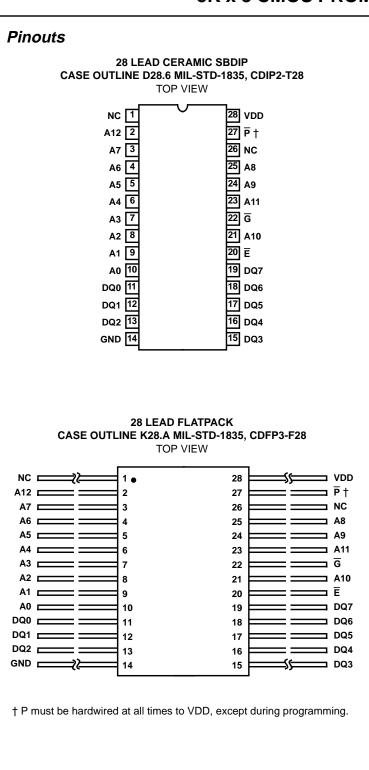
- 1.2 Micron Radiation Hardened Bulk CMOS
- Total Dose 3 x 10⁵ RAD (Si)
- Transient Output Upset >5 x 10⁸ RAD (Si)/s
- LET >100 MEV-cm²/mg
- Fast Access Time 35ns (Typical)
- Single 5V Power Supply
- Single Pulse 10V Field Programmable
- Synchronous Operation
- On-Chip Address Latches
- Three-State Outputs
- NiCr Fuses
- Low Standby Current <500µA (Pre-Rad)
- Low Operating Current <15mA/MHz
- Military Temperature Range -55°C to +125°C

Description

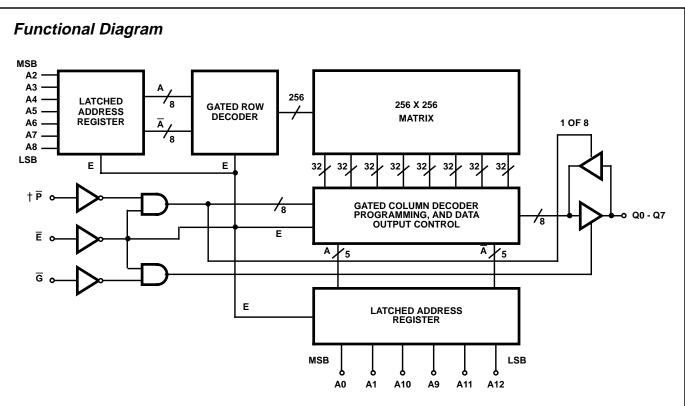
The Intersil HS-6664RH is a radiation hardened 64K CMOS PROM, organized in an 8K word by 8-bit format. The chip is manufactured using a radiation hardened CMOS process, and utilizes synchronous circuit design techniques to achieve high speed performance with very low power dissipation.

On-chip address latches are provided, allowing easy interfacing with microprocessors that use а multiplexed address/data bus structure. The output enable control (\overline{G}) simplifies system interfacing by allowing output data bus control in addition to the chip enable control (\overline{E}). All bits are manufactured storing a logical "0" and can be selectively programmed for a logical "1" at any bit location.

Applications for the HS-6664RH CMOS PROM include low power microprocessor based instrumentation and communications systems, remote data acquisition and processing systems, and processor control storage.



CAUTION: These devices are sensitive to electrostatic discharge; follow proper IC Handling Procedures. http://www.intersil.com or 407-727-9207 | Copyright © Intersil Corporation 1999 840



 \dagger P must be hardwired at all times to VDD, except during programming.

TRUTH TABLE

Ē	G	MODE
0	0	Enabled
0	1	Output Disabled
1	Х	Disabled

Absolute Maximum Ratings

Reliability Information

Supply Voltage (All Voltages Reference to Device GND) +7.0V
Input or Output Voltage
Applied for All Grades GND-0.3V to VDD+0.3V
Storage Temperature Range65°C to +150°C
Junction Temperature
Lead Temperature (Soldering 10s)+300°C
ESD Classification Class 1

	-		
+7.0V	Thermal Resistance	θ _{JA}	$\theta_{\rm JC}$
	Braze Seal DIP Package	40.0°C/W	4.0°C/W
VDD+0.3V	Braze Seal Flatpack Package	53.4°C/W	6.0 ^o C/W
to +150°C	Maximum Package Power Dissipation at +12	25°C	
+175°C	Braze Seal DIP Package		1.75W
+300°C	Braze Seal Flatpack Package		936mW
Class 1	Gate Count	26	,817 Gates
	use permanent damage to the device. This is a stres	, ,	nd operation

CAUTION: Stresses above those listed in "Absolute Maximum Ratings" may cause permanent damage to the device. This is a stress only rating and operation of the device at these or any other conditions above those indicated in the operational sections of this specification is not implied.

Operating Conditions

TABLE 1. DC ELECTRICAL PERFORMANCE CHARACTERISTICS

Device Guaranteed and 100% Tested.

		(NOTES 1, 2)	GROUP A		LIM	IITS	
PARAMETER	SYMBOL	CONDITIONS	SUBGROUPS	TEMPERATURE	MIN	МАХ	UNITS
High Level Output Voltage	VOH1	VDD = 4.5V, IO = -2.0mA	1, 2, 3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	3.5	-	V
Output High Voltage	VOH2	VDD = 4.5V, IO = 100µA	3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	VDD -0.3V	-	V
Low Level Output Voltage	VOL	VDD = 4.5V, IO = 4.8mA	1, 2, 3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	-	0.4	V
High Impedance Output Leakage Current	IOZ	$VDD = 5.5V, \overline{G} = 5.5V,$ VI/O = GND or VDD	1, 2, 3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	-10.0	10.0	μΑ
Input Leakage Current	II	VDD = 5.5V, VI = GND or VDD, \overline{P} Not Tested	1, 2, 3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	-1.0	1.0	μA
Standby Supply Current	IDDSB	VDD = 5.5V, IO = 0mA, VI = VDD or GND	1, 2, 3	$-55^{o}C \leq T_{A} \leq +125^{o}C$	-	500	μΑ
Operating Supply Current	IDDOP	$\label{eq:VDD} \begin{array}{l} VDD = 5.5V, \ \overline{G} = VDD, \\ (Note 3), \ f = 1MHz, \\ IO = 0mA, \ VI = VDD \ or \ GND \end{array}$	1, 2, 3	$-55^{\circ}C \le T_A \le +125^{\circ}C$	-	15	mA
Functional Test	FT	VDD = 4.5V (Note 4)	7, 8A, 8B	$-55^{o}C \leq T_{A} \leq +125^{o}C$	-	-	-

NOTES:

1. All voltages referenced to device GND.

2. All tests performed with $\overline{\mathsf{P}}$ hardwired to VDD.

3. Typical derating = 15mA/MHz increase in IDDOP.

4. Tested as follows: f = 1MHz, VIH = 2.4V, VIL = 0.45V, IOH = -1mA, IOL = +1mA, VOH \ge 1.5V, VOL \le 1.5V.

TABLE 2. AC ELECTRICAL PERFORMANCE CHARACTERISTICS

Device Guaranteed and 100% Tested.

		(NOTES 1, 2, 3)	GROUP A		LIMITS		
PARAMETER	SYMBOL	CONDITIONS	SUBGROUPS	TEMPERATURE	MIN	MAX	UNITS
Output Enable Access Time	TGLQV	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \leq T_A \leq +125^oC$	-	20	ns
Chip Enable Access Time	TELQV	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \le T_A \le +125^oC$	-	60	ns
Address Setup Time	TAVEL	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \le T_A \le +125^oC$	5	-	ns
Address Hold Time	TELAX	VDD = 4.5V and 5.5V	9, 10, 11	$-55^{o}C \leq T_{A} \leq +125^{o}C$	12	-	ns

TABLE 2. AC ELECTRICAL PERFORMANCE CHARACTERISTICS (Continued)

Device Guaranteed and 100% Tested.

		(NOTES 1, 2, 3)	GROUP A		LIM	IITS	
PARAMETER	SYMBOL	CONDITIONS	SUBGROUPS	TEMPERATURE	MIN	MAX	UNITS
Chip Enable Low Width	TELEH	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \le T_A \le +125^oC$	60	-	ns
Chip Enable High Width	TEHEL	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \le T_A \le +125^oC$	20	-	ns
Read Cycle Time	TELEL	VDD = 4.5V and 5.5V	9, 10, 11	$-55^oC \le T_A \le +125^oC$	80	-	ns

NOTES:

1. All voltages referenced to device GND.

2. AC measurements assume transition time \leq 5ns; input levels = 0.0V to 3.0V; timing reference levels = 1.5V; output load = 1 TTL equivalent load and CL \geq 50pF.

3. All tests performed with \overline{P} hardwired to VDD.

4. Address Access Time (TAVQV) = TELQV + TAVEL = 65ns (maximum).

		(NOTE 2)			LIM	IITS	
PARAMETER	SYMBOL	CONDITIONS	NOTES	TEMPERATURE	MIN	МАХ	UNITS
Input Capacitance	CIN	VDD = Open, f = 1MHz	1, 3	T _A = +25 ^o C	-	15	pF
I/O Capacitance	CI/O	VDD = Open, f = 1MHz	1, 3	T _A = +25 ^o C	-	12	pF
Chip Enable Time	TELQX	VDD = 4.5V and 5.5V	3	$-55^oC \le T_A \le +125^oC$	5	-	ns
Output Enable Time	TGLQX	VDD = 4.5V and 5.5V	3	$-55^oC \le T_A \le +125^oC$	5	-	ns
Chip Disable Time	TEHQZ	VDD = 4.5V and 5.5V	3	$-55^oC \le T_A \le +125^oC$	-	15	ns
Output Disable Time	TGHQZ	VDD = 4.5V and 5.5V	3	$-55^oC \le T_A \le +125^oC$	-	15	ns

TABLE 3. ELECTRICAL PERFORMANCE CHARACTERISTICS, AC AND DC

NOTES:

1. All measurements referenced to device GND.

2. All tests performed with \overline{P} hardwired to VDD.

3. The parameters listed are controlled via design or process parameters and are not directly tested. These parameters are characterized upon initial design and after design or process changes which would affect these characteristics.

TABLE 4. POST 100K RAD AC AND DC ELECTRICAL PERFORMANCE CHARACTERISTICS

NOTE: All AC and DC parameters are tested at the +25°C pre-irradiation limits.

PARAMETER	SYMBOL	DELTA LIMITS
Standby Supply Current	IDDSB	±50μA
Input Leakage Current	IOZ	±1μA
	II	±100nA
Output Low Voltage	VOL	±60mV
Output High Voltage	VOH	±400mV

TABLE 5. BURN-IN DELTA PARAMETERS (+25°C)

CONFORMAN	NCE GROUPS	METHOD	-Q SUBGROUPS	-8 SUBGROUPS
Initial Test		100%/5004	1, 7, 9	1, 7, 9
Interim Test		100%/5004	1, 7, 9	1, 7, 9
PDA 1 and 2		100%/5004	1, 7, Δ	1, 7
Final Test		100%/5004	2, 3, 8A, 8B, 10, 11	2, 3, 8A, 8B, 10, 11
Group A		Samples/5005	1, 2, 3, 7, 8A, 8B, 9, 10, 11	1, 2, 3, 7, 8A, 8B, 9, 10, 11
Group B	B5	Samples/5005	1, 2, 3, 7, 8A, 8B	N/A
(*Optional)	Others	Samples/5005	1, 7,9	N/A
Group C (Optic	onal)	Samples/5005	N/A	1, 7, 9
Group D (Optic	onal)	Samples/5005	1, 7, 9	1, 7, 9
Group E, Subgroup 2 (Note 1)		Samples/5005	1, 7, 9	1, 7, 9

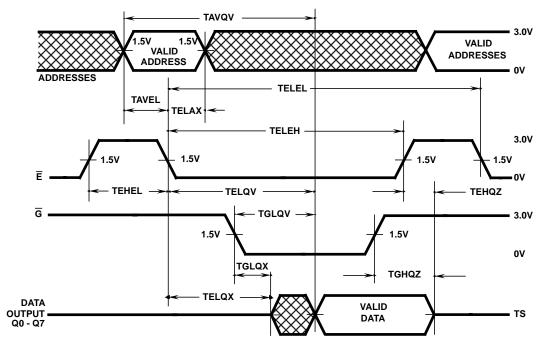
TABLE 6. APPLICABLE SUBGROUPS

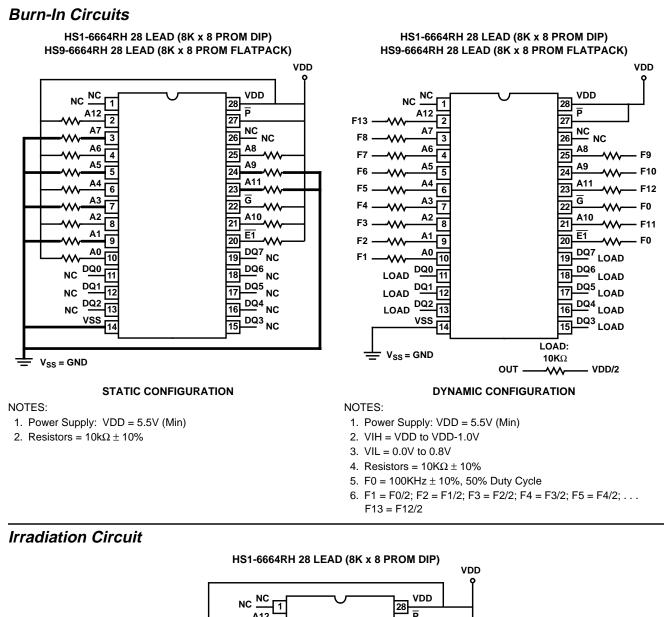
NOTE:

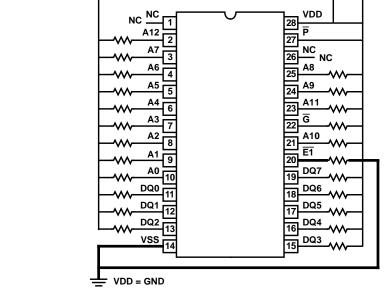
1. Intersil may exercise its option to perform to a small lot sampling plan of 5 units per lot.

Timing Waveform

READ CYCLE







NOTES:

- 1. Power Supply: VDD = $5.5V \pm 0.5V$
- 2. All Resistors = $47K\Omega \pm 10\%$

Intersil - Space Level (-Q) Product Flow (Note 1)

SEM - Traceable to Diffusion Method 2018	Alternate Group A - Subgroups 1, 7, 9; Method 5005; Para
Wafer Lot Acceptance Method 5007	3.5.1.1
Internal Visual Inspection Method 2010, Condition A	Burn-In Delta Calculation (T0 - T2)
Gamma Radiation Assurance Tests Method 1019	PDA Calculation 3% Subgroup 7
Nondestructive Bond Pull Method 2023	5% Subgroups 1, 7, Δ
Customer Pre-Cap Visual Inspection (Note 2)	Electrical Tests - Subgroup 3; Read and Record
Temperature Cycling Method 1010, Condition C	Alternate Group A - Subgroups 3, 8B, 11; Method 5005; Para
Constant Acceleration Method 2001, Condition E Min, Y1	3.5.1.1
Particle Impact Noise Detection Method 2020, Condition A	Marking
Electrical Tests (Intersil' Option)	Electrical Tests - Subgroup 2; Read and Record
Serialization	Alternate Group A - Subgroups 2, 8A, 10; Method 5005;
X-Ray Inspection Method 2012	Para 3.5.1.1
Electrical Tests - Subgroup 1; Read and Record (T0)	Gross Leak Tests Method 1014, 100%
Static Burn-In Method 1015, Condition B, 72 Hrs, +125°C Min.	Fine Leak Tests Method 1014, 100%
Interim 1 Electrical Tests - Subgroup 1; Read and Record (T1)	Customer Source Inspection (Note 2)
Burn-In Delta Calculation (T0 -T1)	Group B Inspection Method 5005 (Note 2)
PDA Calculation 3% Subgroup 7	End-Point Electrical Parameters: B-5 - Subgroups 1, 2, 3,
5% Subgroups 1, 7, A	7, 8A, 8B, 9, 10, 11; B-6 - Subgroups 1, 7, 9
nterim 1 Electrical Tests - Subgroup 1; Read and Record (T1)	Group B Inspection Method 5005 (Note 2)
Burn-In Delta Calculation (T0 -T1)	End-Point Electrical Parameters: B-5 - Subgroups 1, 2, 3,
Dynamic Burn-In Method 1015, Condition D, 240 Hrs, +125°C (Note 3) Interim 2 Electrical Tests - Subgroup 1; Read and Record (T2) NOTES:	End-Point Electrical Parameters: Subgroups 1, 7, 9 External Visual Inspection Method 2009 Data Package Generation (Note 4)

1. The notes of Method 5004, Table 1 shall apply; Unless Otherwise Specified.

2. These steps are optional, and should be listed on the individual purchase order(s), when required.

3. Intersil reserves the right of performing burn-in time temperature regression as defined by Table 1 of Method 1015.

 Data package contains: Assembly Attributes (post seal) 	Radiation Testing Certificate of Conformance Wafer Lot Acceptance Report (Including SEM Report)
Test Attributes (includes Group A)	X-Ray Report and Film
Shippable Serial Number List	Test Variables Data

Intersil -8 Product Flow

Internal Visual Inspection Method 2010 Condition B Alternate Gamma Radiation Assurance Tests Method 1019 Customer Pre-Cap Visual Inspection (Note 1) Temperature Cycling Method 1010, Condition C Fine and Gross Leak Tests Method 1014 Constant Acceleration Method 2001 Y1 30KG Initial Electrical Tests	PDA Calculation 5% Subgroups 1, 7 Electrical Tests +125°C, -55°C Group A Inspection Method 5005. 5% PDA (Note 3) Brand Customer Source Inspection (Note 1) Group B Inspection Method 5005 (Notes 1, 2) Group C Inspection Method 5005 (Notes 1, 2)
Dynamic Burn-In Method 1015, Condition D, 160 Hrs, +125°C	External Visual Inspection Method 2009
+25 ^o C Electrical Tests - Subgroups 1, 7, 9	Data Package Generation (Note 4)

NOTES:

1. These steps are optional, and must be negotiated as part of order.

2. Group B, C and D data package contains Attributes Data.

3. Intersil reserves the right to perform Alternate Group A. The 5% PDA is still applicable.

4. '-8' Data package contains:

Assembly Attributes (post seal) Test Attributes (includes Group A) Radiation Testing Certificate of Conformance Certificate of Conformance (as found on shipper)

Metallization Topology

DIE DIMENSIONS:

271 x 307 x 19 $\pm 1 \text{mils}$

METALLIZATION;

M1: $6k\dot{A} \pm 1k\dot{A} Si/Al/Cu$ $2k\dot{A} \pm 500\dot{A} TiW$ M2: $10k\dot{A} \pm 2k\dot{A}Si/Al/Cu$

GLASSIVATION:

Type: SiO₂ Thickness: $8k\dot{A} \pm 1k\dot{A}$

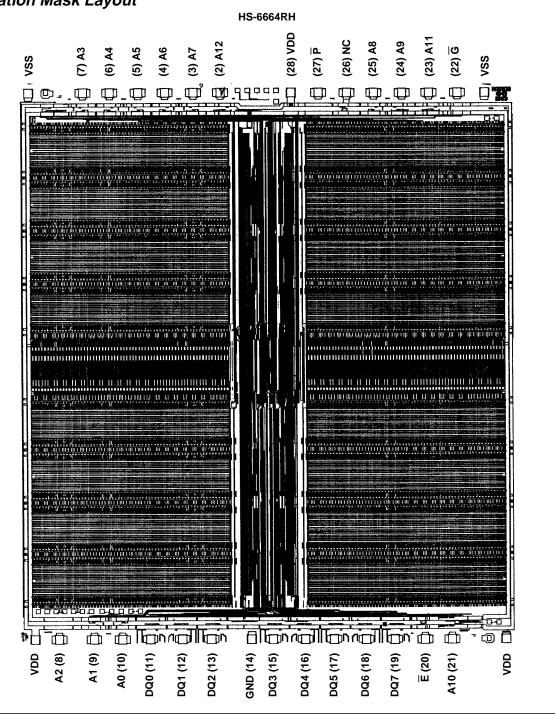
Metallization Mask Layout

WORST CASE CURRENT DENSITY: $2 \times 10^5 \text{ A/cm}^2$

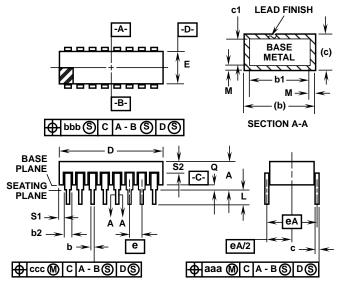
SUBSTRATE POTENTIAL: VDD

TRANSISTOR COUNT: 110, 874

GATE COUNT: 27, 719 (Based on 2-Input NAND)



Packaging



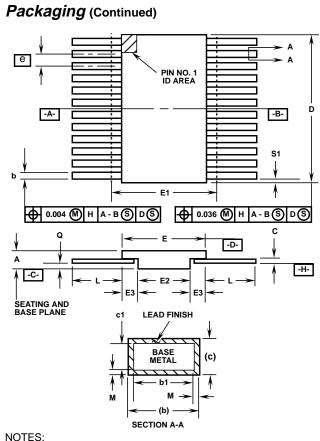
NOTES:

- 1. Index area: A notch or a pin one identification mark shall be located adjacent to pin one and shall be located within the shaded area shown. The manufacturer's identification shall not be used as a pin one identification mark.
- 2. The maximum limits of lead dimensions b and c or M shall be measured at the centroid of the finished lead surfaces, when solder dip or tin plate lead finish is applied.
- 3. Dimensions b1 and c1 apply to lead base metal only. Dimension M applies to lead plating and finish thickness.
- 4. Corner leads (1, N, N/2, and N/2+1) may be configured with a partial lead paddle. For this configuration dimension b3 replaces dimension b2.
- 5. Dimension Q shall be measured from the seating plane to the base plane.
- 6. Measure dimension S1 at all four corners.
- 7. Measure dimension S2 from the top of the ceramic body to the nearest metallization or lead.
- 8. N is the maximum number of terminal positions.
- 9. Braze fillets shall be concave.
- 10. Dimensioning and tolerancing per ANSI Y14.5M 1982.
- 11. Controlling dimension: INCH.

D28.6 MIL-STD-1835 CDIP2-T28 (D-10, CONFIGURATION C) 28 LEAD CERAMIC DUAL-IN-LINE METAL SEAL PACKAGE

	INC	HES	MILLIM			
SYMBOL	MIN	MAX	MIN MAX		NOTES	
A	-	0.232	-	5.92	-	
b	0.014	0.026	0.36	0.66	2	
b1	0.014	0.023	0.36	0.58	3	
b2	0.045	0.065	1.14	1.65	-	
b3	0.023	0.045	0.58	1.14	4	
с	0.008	0.018	0.20	0.46	2	
c1	0.008	0.015	0.20	0.38	3	
D	-	1.490	-	37.85	-	
E	0.500	0.610	12.70	15.49	-	
е	0.100 BSC		2.54 BSC		-	
eA	0.600 BSC		15.24 BSC		-	
eA/2	0.300 BSC		7.62 BSC		-	
L	0.125	0.200	3.18	5.08	-	
Q	0.015	0.060	0.38	1.52	5	
S1	0.005	-	0.13	-	6	
S2	0.005	-	0.13	-	7	
α	90 ⁰	105 ⁰	90 ⁰	105 ⁰	-	
aaa	-	0.015	-	0.38	-	
bbb	-	0.030	-	0.76	-	
ссс	-	0.010	-	0.25	-	
М	-	0.0015	-	0.038	2	
N	28		2	8		

Rev. 0 5/18/94



NO	165:
1.	Index area: A notch or a pin one identification mark shall be locat-
	ed adjacent to pin one and shall be located within the shaded
	area shown. The manufacturer's identification shall not be used
	as a pin one identification mark. Alternately, a tab (dimension k)
	may be used to identify pin one.

- 2. If a pin one identification mark is used in addition to a tab, the limits of dimension k do not apply.
- 3. This dimension allows for off-center lid, meniscus, and glass overrun.
- 4. Dimensions b1 and c1 apply to lead base metal only. Dimension M applies to lead plating and finish thickness. The maximum limits of lead dimensions b and c or M shall be measured at the centroid of the finished lead surfaces, when solder dip or tin plate lead finish is applied.
- 5. N is the maximum number of terminal positions.
- 6. Measure dimension S1 at all four corners.
- 7. For bottom-brazed lead packages, no organic or polymeric materials shall be molded to the bottom of the package to cover the leads.
- Dimension Q shall be measured at the point of exit (beyond the meniscus) of the lead from the body. Dimension Q minimum shall be reduced by 0.0015 inch (0.038mm) maximum when solder dip lead finish is applied.
- 9. Dimensioning and tolerancing per ANSI Y14.5M 1982.
- 10. Controlling dimension: INCH.

K28.A MIL-STD-1835 CDFP3-F28 (F-11A, CONFIGURATION B) 28 LEAD CERAMIC METAL SEAL FLATPACK PACKAGE

	INCHES MILLIMETERS					
SYMBOL	MIN	MAX	MIN	MAX	NOTES	
А	0.045	0.115	1.14	2.92	-	
b	0.015	0.022	0.38	0.56	-	
b1	0.015	0.019	0.38	0.48	-	
С	0.004	0.009	0.10	0.23	-	
c1	0.004	0.006	0.10	0.15	-	
D	-	0.740	-	18.80	3	
E	0.460	0.520	11.68	13.21	-	
E1	-	0.550	-	13.97	3	
E2	0.180	-	4.57	-	-	
E3	0.030	-	0.76	-	7	
е	0.050 BSC		1.27 BSC		-	
k	0.008	0.015	0.20	0.38	2	
L	0.250	0.370	6.35	9.40	-	
Q	0.026	0.045	0.66	1.14	8	
S1	0.00	-	0.00	-	6	
М	-	0.0015	-	0.04	-	
Ν	28		2	-		

Rev. 0 5/18/94



HS-6664RH

DESIGN INFORMATION

September 1995

8K x 8 CMOS PROM

The information contained in this section has been developed through characterization by Intersil Semiconductor and is for use as application and design information only. No guarantee is implied.

PROGRAMMING SPECIFICATIONS

Background Information HS-6664RH Programming

PARAMETER	SYMBOL	MIN	ТҮР	МАХ	UNITS	NOTES
Input "0"	VIL	0.0	0.2	0.8	V	
Voltage "1"	VIH	VDD-2	VDD	VDD+0.3	V	6
Programming VDD	VDDPROG	9.0	9.0	9.0	V	2
Operating VDD	VDD1	4.5	5.5	5.5	V	
Special Verify	VDD2	4.0	-	6.0	V	3
Delay Time	td	1.0	1.0	-	μs	
Rise Time	tr	1.0	10.0	10.0	μs	
Fall Time	tf	1.0	10.0	10.0	μs	
Chip Enable Pulse Width	TEHEL	20	-	-	ns	
Address Valid to Chip Enable Low Time	TAVEL	0	-	-	ns	
Chip Enable Low to Output Valid Time	TELQV	-	-	60	ns	
Programming Pulse Width	tpw	90	100	110	μs	4
Input Leakage at VDD = VDDPROG	tIP	-10	+1.0	10	μΑ	
Data Output Current at VDD = VDDPROG	IOP	-	-5.0	-10	mA	
Output Pull-Up Resistor	Rn	5	10	15	kΩ	5
Ambient Temperature	T _A	-	25	-	°C	

NOTES:

1. All inputs must track VDD (pin 28) within these limits.

2. VDDPROG must be capable of supplying 500mA. VDDPROG Power Supply tolerance $\pm 3\%$ (Max.)

3. See Steps 22 through 29 of the Programming Algorithm.

4. See Step 11 of the Programming Algorithm.

5. All outputs should be pulled up to VDD through a resistor of value Rn.

6. Except during programming (See Programming Cycle Waveforms).

DESIGN INFORMATION (Continued)

The information contained in this section has been developed through characterization by Intersil Semiconductor and is for use as application and design information only. No guarantee is implied.

Background Information Programming

The HS-6664 CMOS PROM is manufactured with all bits containing a logical zero (output low). Any bit can be programmed selectively to a logical one (output high) state by following the procedure shown below. To accomplish this, a programmer can be built that meets the specifications shown, or use of an approved commercial programmer is recommended.

Programming Sequence of Events

- 1. Apply a voltage of VDD1 to VDD of the PROM.
- 2. Read all fuse locations to verify that the PROM is blank (output low).
- 3. Place the PROM in the initial state for programming: $\overline{E} = VIH, \overline{P} = VIH, \overline{G} = VIL.$
- 4. Apply the correct binary address for the word to be programmed. No inputs should be left open circuit.
- 5. After a delay of td, apply voltage of VIL to \overline{E} (pin 20) to access the addressed word.
- 6. The address may be held through the cycle, but must be held valid at least for a time equal to td after the falling edge of \overline{E} . None of the inputs should be allowed to float to an invalid logic level.
- 7. After a delay of td, disable the outputs by applying a voltage of VIH to \overline{G} (pin 22).
- 8. After a delay of td, apply voltage of VIL to \overline{P} (pin 27).
- 9. After delay of td, raise VDD (pin 28) to VDDPROG with a rise time of tr. All outputs at VIH should track VDD within VDD-2.0V to VDD+0.3V. This could be accomplished by pulling outputs at VIH to VDD through pull-up resistors of value Rn.
- 10. After a delay of td, pull the output which corresponds to the bit to be programmed to VIL. Only one bit should be programmed at a time.
- 11. After a delay of tpw, allow the output to be pulled to VIH through pull-up resistor Rn.
- 12. After a delay of td, reduce VDD (pin 28) to VDD1 with a fall time of tf. All outputs at VIH should track VDD with VDD-2.0V to VDD+0.3V. This could be accomplished by pulling outputs at VIH to VDD through pull-up resistors of value Rn.
- 13. Apply a voltage of VIH to \overline{P} (pin 27).
- 14. After a delay of td, apply a voltage of VIL to \overline{G} (pin 22).

- 15. After a delay of td, examine the outputs for correct data. If any location verifies incorrectly, it should be considered a programming reject.
- 16. Repeat steps 3 through 15 for all other bits to be programmed in the PROM.

Post-Programming Verification

17. Place the PROM in the post-programming verification mode:

 $\overline{E} = VIH, \overline{G} = VIL, \overline{P} = VIH, VDD (pin 28) = VDD1.$

- 18. Apply the correct binary address of the word to be verified to the PROM.
- 19. After a delay of td, apply a voltage of VIL to \overline{E} (pin 20).
- 20. After a delay of td, examine the outputs for correct data. If any location fails to verify correctly, the PROM should be considered a programming reject.
- 21. Repeat steps 17 through 20 for all possible programming locations.

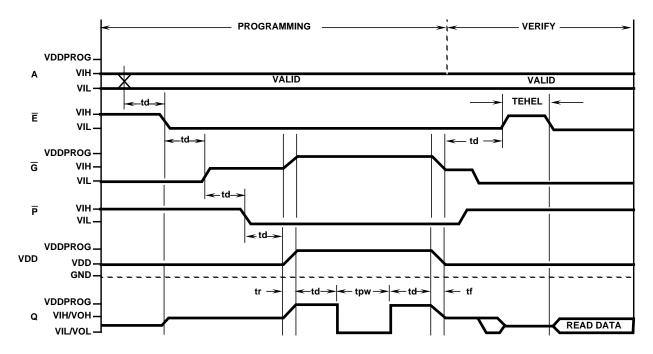
Post-Programming Read

- 22. Apply a voltage of VDD2 = 4.0V to VDD (pin 28).
- 23. After a delay of td, apply a voltage of VIH to \overline{E} (pin 20).
- 24. Apply the correct binary address of the word to be read.
- 25. After a delay of TAVEL, apply a voltage of VIL to \overline{E} (pin 20).
- 26. After a delay of TELQV, examine the outputs for correct data. If any location fails to verify correctly, the PROM should be considered a programming reject.
- 27. Repeat steps 23 through 26 for all address locations.
- 28. Apply a voltage of VDD2 = 6.0V to VDD (pin 28).
- 29. Repeat steps 23 through 26 for all address locations.

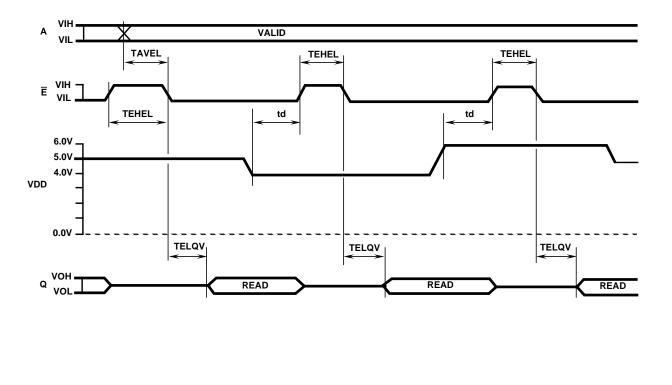
DESIGN INFORMATION (Continued)

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HS-6664RH PROGRAMMING CYCLE



HS-6664RH POST PROGRAMMING VERIFY CYCLE



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